

Development of High-performance Niobium-3 Tin Cavities at Cornell University

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| | Nb | Nb ₃ Sn | |
|---|-------------------|----------------------|----------------------------|
| Critical Temperature (<i>T_C</i>) | 9 K | 18 K | |
| Q ₀ at 4.2K | 6×10^{8} | 6 × 10 ¹⁰ | 5 |
| Superheating Field (<i>B</i> _{sh}) | 240 mT | 420 mT | |
| Max. E _{acc} | 55 MV/m | 100 MV/m | $\boldsymbol{\mathcal{S}}$ |

*Q*₀ given for 1.3 GHz single-cell ILC-shape cavities

Higher operating temperature ≡ Lower cooling cost and complexity

Higher superheating field B_{sh} = higher accelerating gradients: $E_{acc,max} \propto B_{sh}$











State-of-the-Art: Thermal Vapor Diffusion



"Wuppertal" configuration (secondary heater for the tin source)







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S. Posen and M. Liepe, Phys. Rev. ST Accel. Beams 15, 112001 (2014)

State-of-the-art Performance



- \rightarrow Reproducible performance of ~4 K operation with $Q_0 > 10^{10}$ at typical CW operating fields.
- \rightarrow Current quench fields: 16-24 MV/m (FNAL holds world record)



(Note: Plots are for single cell cavities)

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Efforts continue worldwide to push the limits of Nb3Sn even further!

Some presentations here at SRF'23: TUPTB009, TUPTB010, TUPTB014, TUPTB015, TUPTB020, TUPTB065, WEPWB126

Limitations



- 1. Tin depleted regions
 - → Tin depleted regions have a low critical temperature



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- 2. Uniformity of thickness of film
 - → Thinner patches expose Nb-Nb3Sn interface (tin depleted)



Limitations



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5

8

- **Tin depleted regions** 1.
 - Tin depleted regions have a low critical temperature
- Uniformity of thickness of film 2.
 - Thinner patches expose Nb-Nb3Sn \rightarrow interface (tin depleted)



1 µm 20Surface roughness 3. 18 Can cause field enhancement and vortex nucleation _ 16 Critical temperature [K 14 12 $T_c(\beta)$ linear 10 Moore 1979 ~1µm $T_c(\beta)$ Boltzmann function Devantay 1981 R. D. Porter, Ph.D. thesis, 0 2 Devantay 1981 (after Flükiger 1981) Phys. Dept., Cornell University, Ithaca, United 1.5 17 18 19 20 21 22 23 24 25 26 States, 2021 x 10 x 10⁻⁵ Atomic Sn content [%] 0.5 SRF'23 | WEIAA04 0 0 y (m) x (m)









Why thin films?



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2. Thinner films are smoother! (Pudasaini, WEIAA03)

The FNAL cavity which reached 24 MV/m had a shiny thin-film Nb3Sn coating.SRF'23 | WEIAA04(S. Posen, https://doi.org/10.1088/1361-6668/abc7f7)

Thin Film Cavity



New recipe (inspired by FNAL):

- \rightarrow Increase Sn vapor pressure from start
- \rightarrow Shorter coating time
- \rightarrow Skip the 5-hour nucleation



Thin Film Cavity



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- $\rightarrow\,$ Shorter coating time
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Result:

- → Lower surface roughness!
- $\rightarrow \mbox{Lower BCS resistance, but higher } R_0 \mbox{ and similar quench fields (suspect due to patchy regions)}$



Thin Film Cavity









Vapor Diffusion – Nucleation Study



Goal: Minimize tin depleted regions and achieve a smooth Nb₃Sn film.

Motivation: The surface of the niobium oxide structure plays an important role in the nucleation of SnCl₂.



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SnCl₂ molecules with (right) and without (left) passivating OH groups covering the surface







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N. Sitaraman, "Theory work on SRF materials", Ph.D. thesi Phys, Dept., Cornell University, Ithaca, United States, 2022



Can we experimentally promote more uniform nucleation through adding or removing OH groups from the oxide?

Sample Preparation

Samples were electropolished, anodized and soaked in chemical treatments in a nitrogen atmosphere.



The samples (control sample not shown) after being soaked in the chemical treatments.



The furnace run was stopped after the nucleation step and the samples were taken out for surface characterization and analysis.

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- 1. Scanning Electron Microscopy (SEM)
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- 2. Energy Dispersive Spectroscopy (EDS)
 - → extract information about elemental composition (Sn:Nb atomic





Establish relative comparison of the Sn:Nb at. % ratio among our samples.

neighbors

Distribution of Nucleation Sites







Distribution of Nucleation Sites





Distribution of Nucleation Sites





Predicting Thin Film Regions



Nb₃Sn grains have ~1 μ m² area.



We want <u>at least</u> 1 nucleation site per intended grain:

- How many imaged areas had a density of less than one particle per 1 μm² area?
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Are these droplets actually tin?













Cornell Nb₃Sn Electroplating Breakthrough



- Promotes uniform distribution of nucleation (
 surface roughness)
- Provides sufficient Sn supply in critical times



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Sample Studies



30

- 25

²⁰ us

Sample studies have shown low surface roughness and little variation in Sn concentration with depth.





Images from Zhaslan Baraissov

This method was developed by Zeming Sun Sun et al., doi: 10.48550/arXiv.2302.02054

SRF'23 | WEIAA04

Scaling up to 1.3 GHz cavity





1.3 GHz cavity

Post-annealing





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Chemical Vapor Deposition (CVD)



CVD is an alternative method for depositing thin films

 \rightarrow allows for precise control over the properties of the deposited films

CVD furnace is being commissioned at Cornell University as a potential path to grow high-quality Nb₃Sn films (among other SRF materials)

→ See Gabriel Gaitan's poster MOPMB015 *"Development of a Plasma-Enhanced Chemical Vapor Deposition System for High-Performance SRE Cavities"*







Chemical pre-treatments of the niobium oxide have an effect in the nucleation of tin in vapor-diffused-based growth \Rightarrow new knob to turn to achieve thinner, smoother films of uniform thickness and composition

Electrochemical deposition (followed by thermal annealing): First-ever alternative growth method to achieve such high performance ($Q_0 > 10^{10}$ and low BCS resistance)



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